



Thin Film Solutions



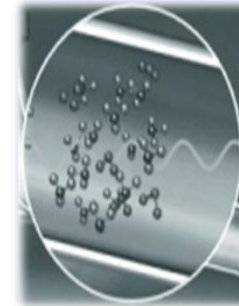
Bulk and
special gas
distribution



Chemical supply
systems



Engineering,
design and
development

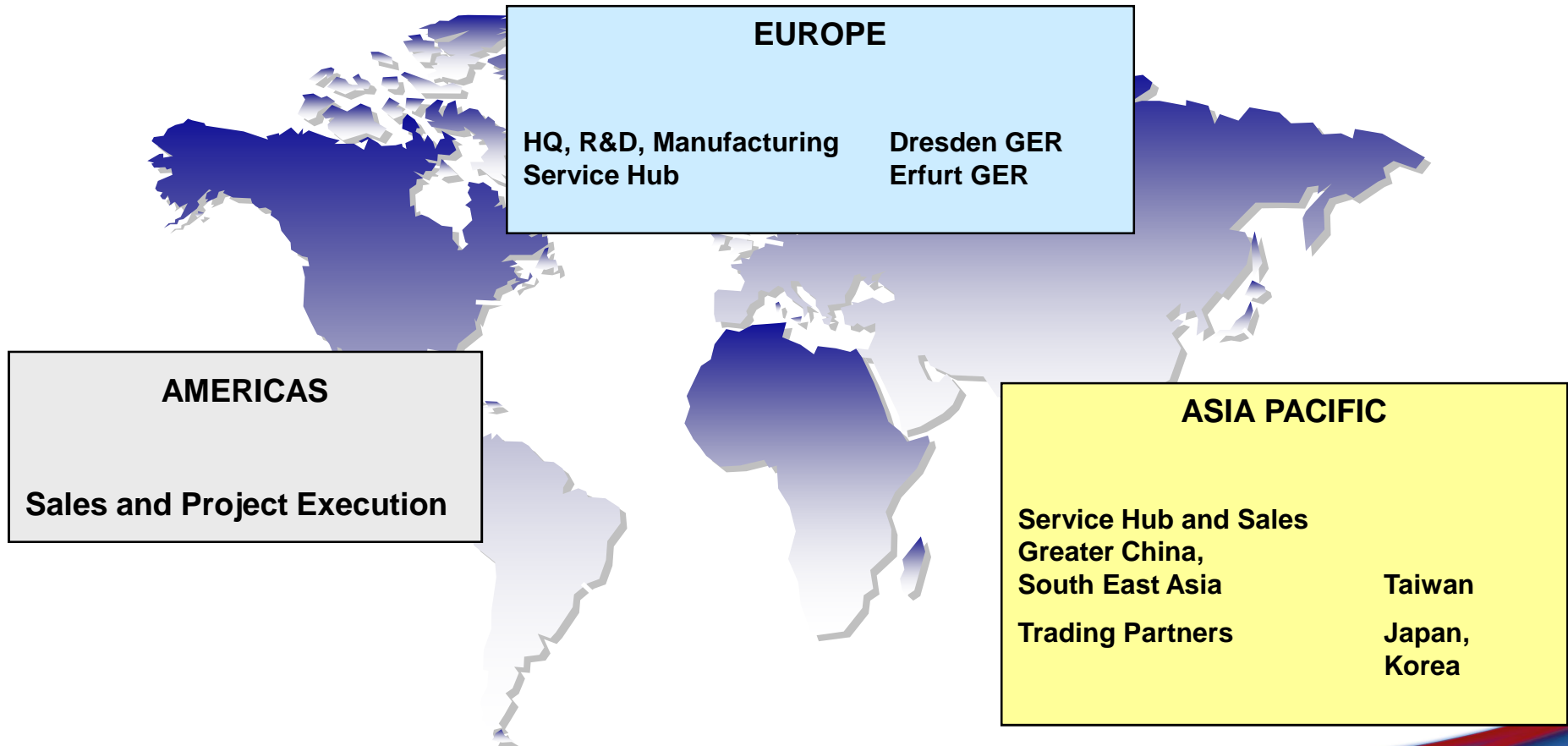


Service and
operation



Process vacuum
and exhaust systems



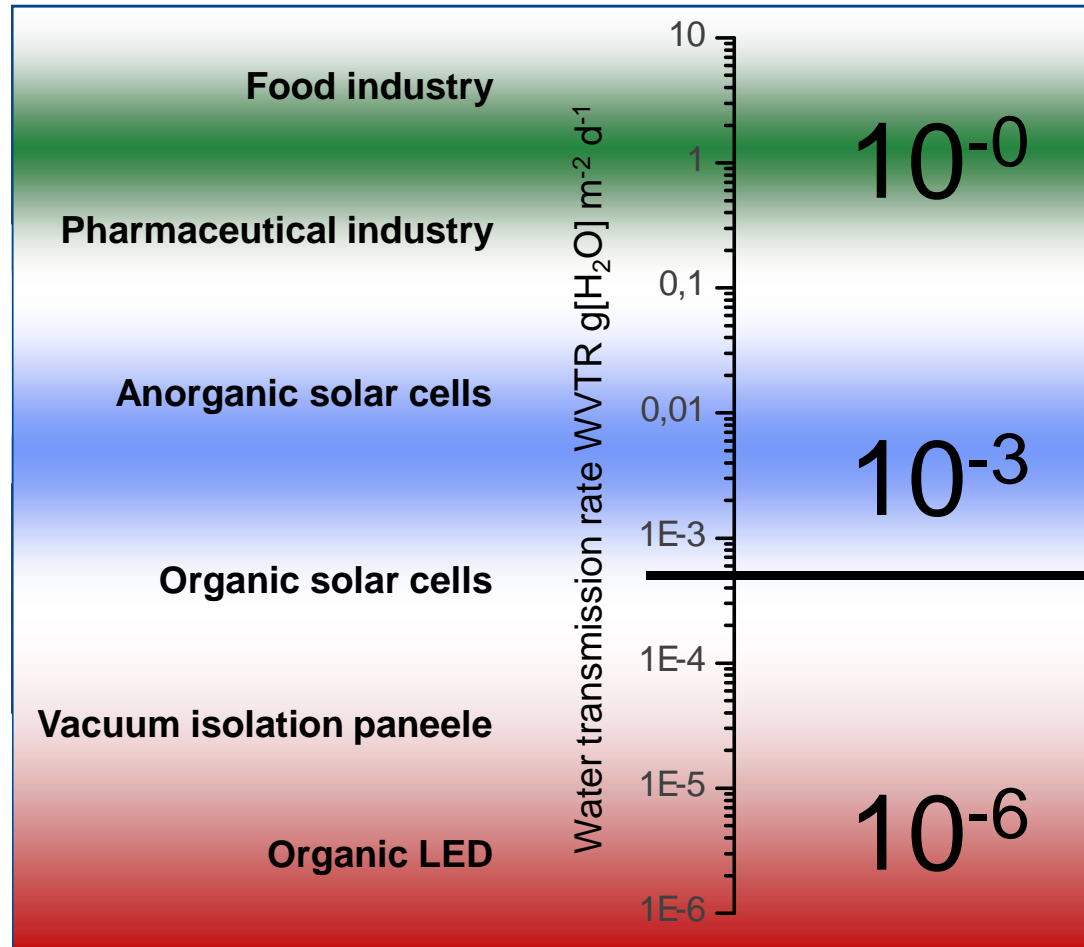
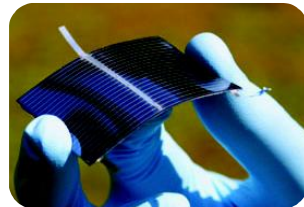


- HiBarSens
- Special equipment for thin film deposition (excerpt...)
 - DEZn supply for ZnO TCO layers
 - TMAI supply for AlOx backside passivation
 - PECVD for barrier layers – HMDSO...
 - Enabling III/V on Si
 - Special liquid Indium-MO source supply systems for IGZO
 - LED supply systems for MO-III (TMGa)
 -

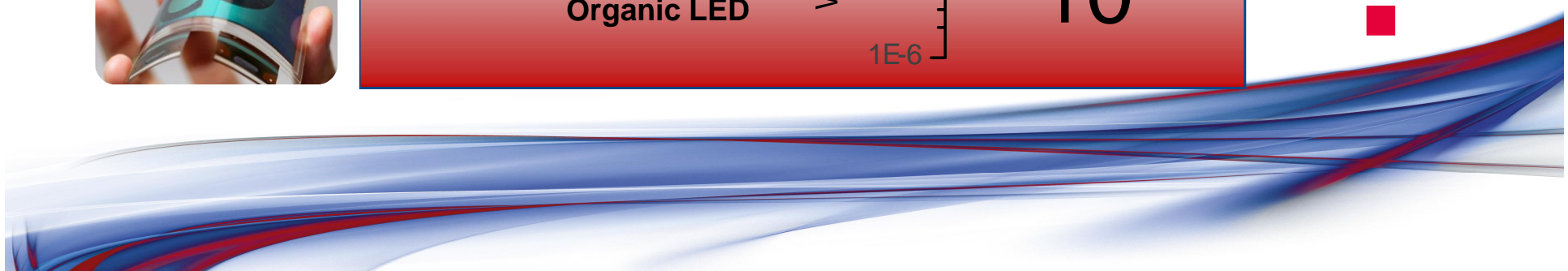


HiBar *ens*
HBS 18-1

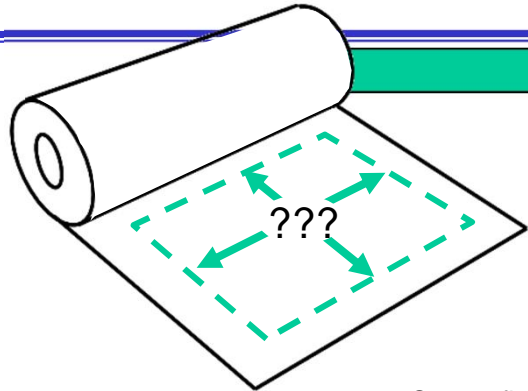
Water Vapor
Permeation
Measurement System



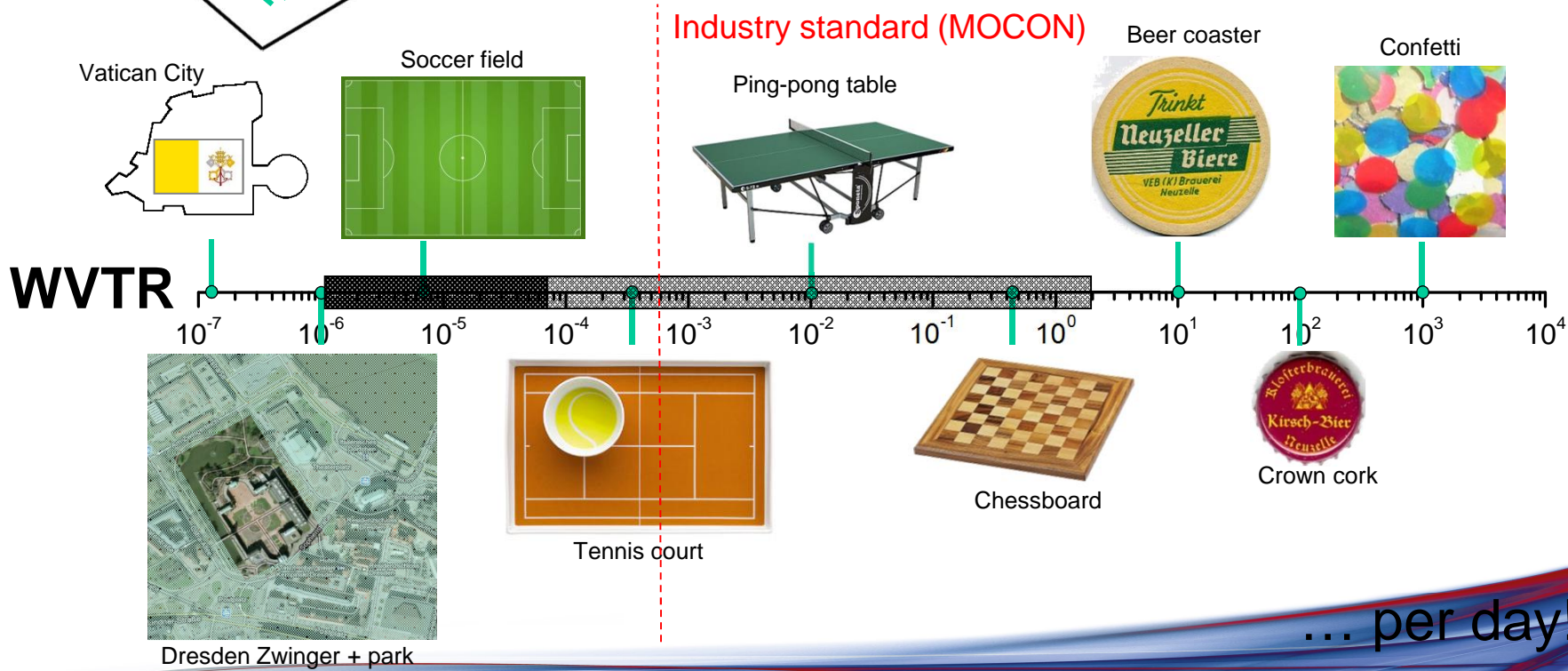
currently measurable by standard methods



WVTR of $10^x \text{ g m}^{-2} \text{ d}^{-1}$ is equivalent to:

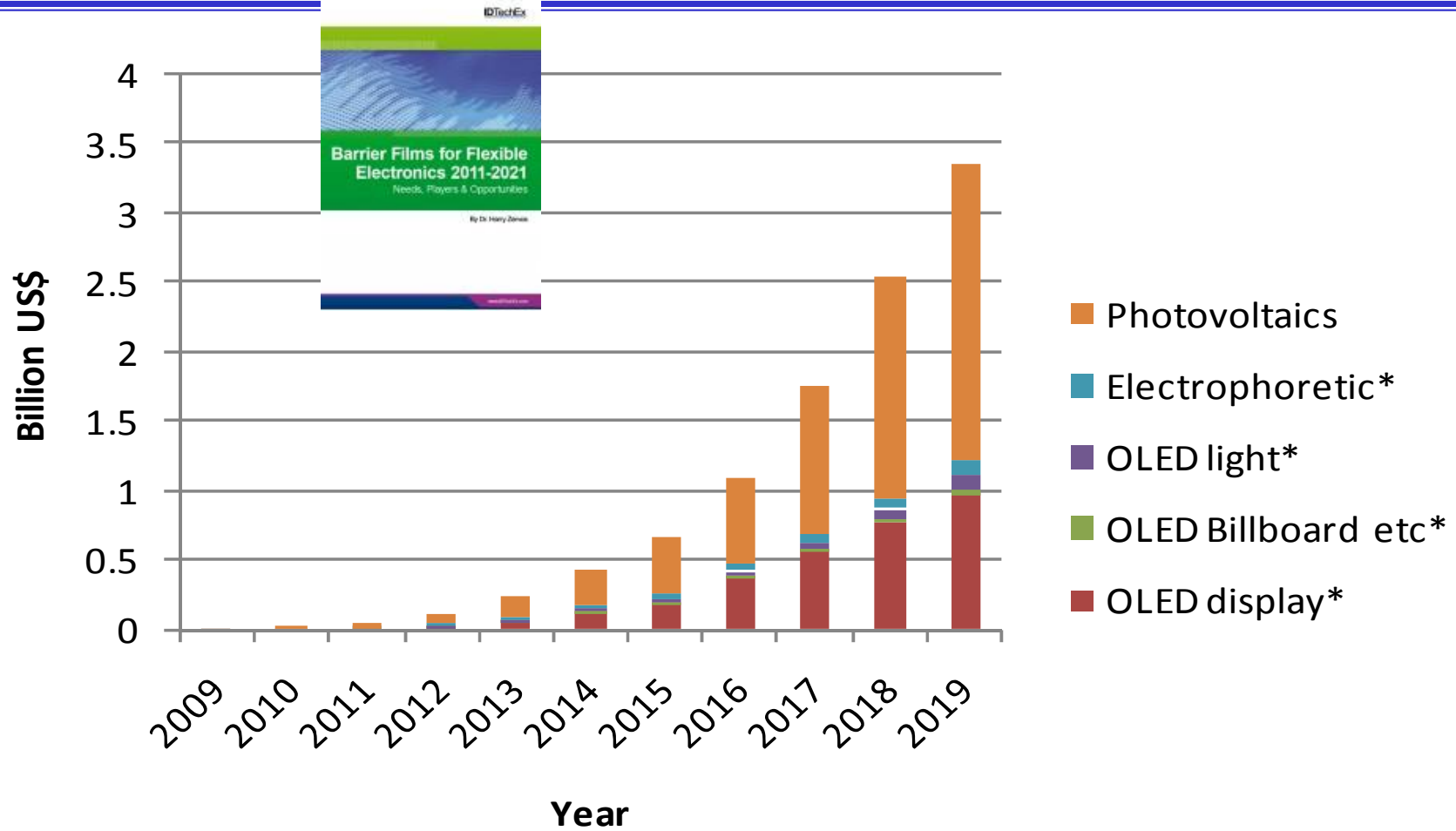


One water drop ...
... at a sample area of:



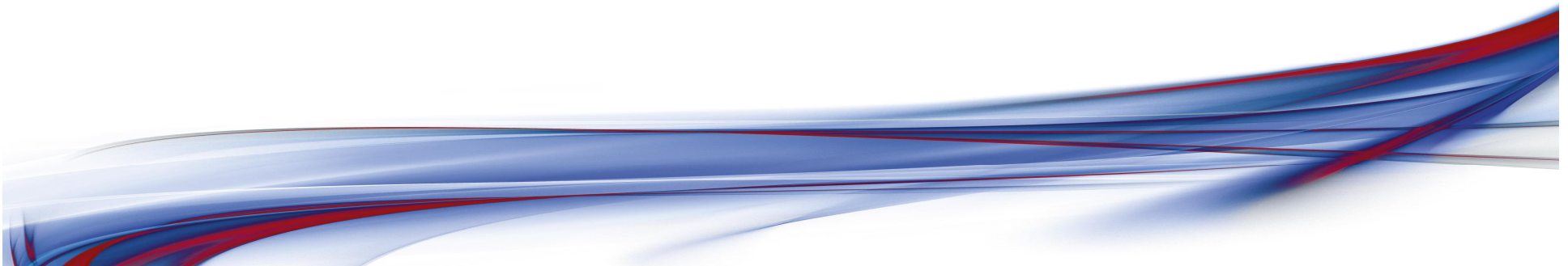
... per day!

Market forecast for ultra barrier films



Harry Zervos: "Barrier Films for Flexible Electronics: Needs, Players & Opportunities". IDTechEx Ltd., December 2008)

BASICS

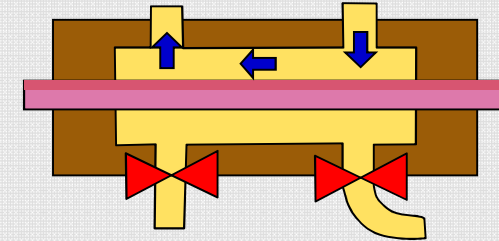
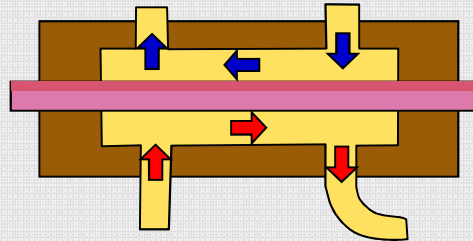


Measuring modes: dynamic vs. static

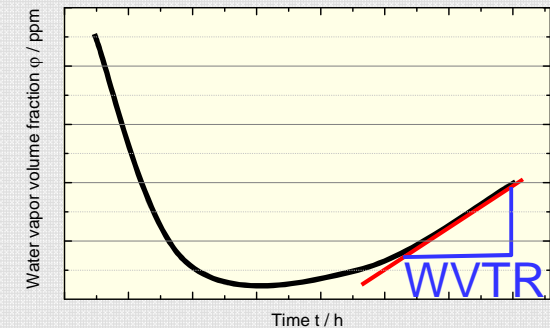
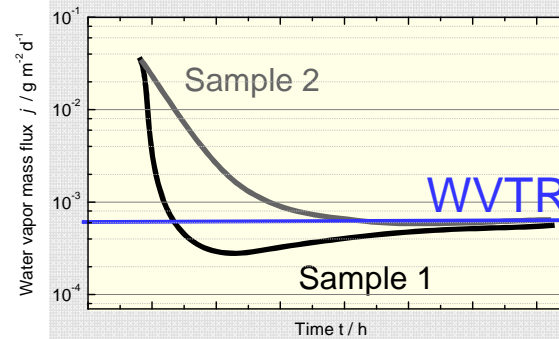
■ Measuring setup:

dynamic (isostatic)

static (quasi isostatic)



■ Typical chart



■ Calculation of WVTR

$$WVTR = \frac{\dot{V}_{Purge} \cdot M_{H_2O}}{R \cdot T \cdot A_{sample}} \cdot p \cdot \frac{\phi}{1 - \phi}$$

$$WVTR - \dot{n}_{sorp} = \frac{V_{cell}}{R \cdot T} \cdot \frac{M_{H_2O}}{A_{sample}} \cdot p \cdot \frac{\Delta \phi}{\Delta t}$$

(ϕ ... Water vapor volume fraction (measured by LDS))

- Tunable diode laser absorption spectroscopy (TDLAS)

Limit of Detection LOD(H₂O):

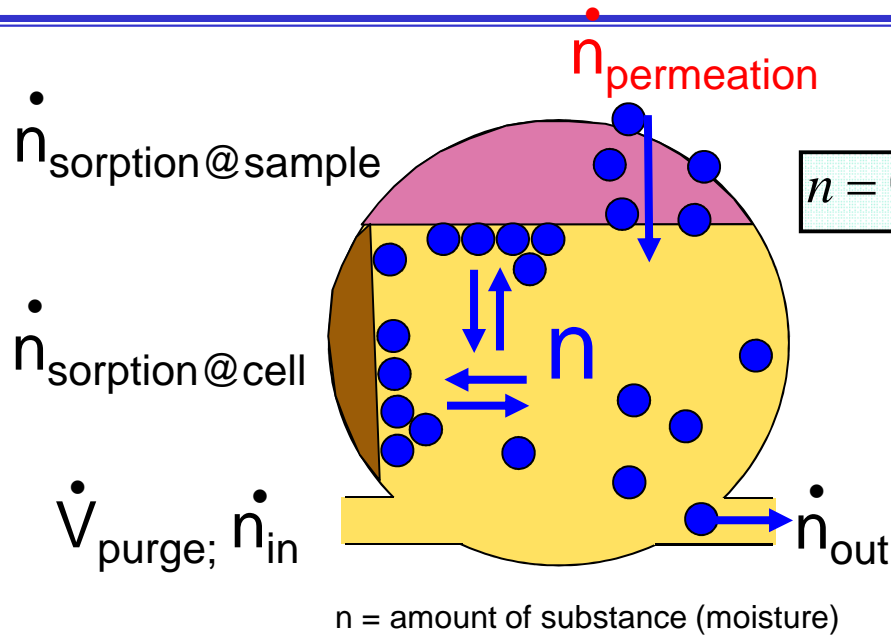
100 ppb m

- Measuring setup:

- Sample size
- Chamber volume
- Accumulation time
- Purge flow
- Optical path length

	dynamic	static
		100 cm ²
		0,1 l
	-	10 h
	0,01 slm	-
		1 m
	↓	↓
	~ 10 ⁻⁵ g m ⁻² d ⁻¹	~ 10 ⁻⁶ g m ⁻² d ⁻¹
	!Theoretical estimations!	

- WVTR < 10⁻⁴ g m⁻² d⁻¹ are measurable

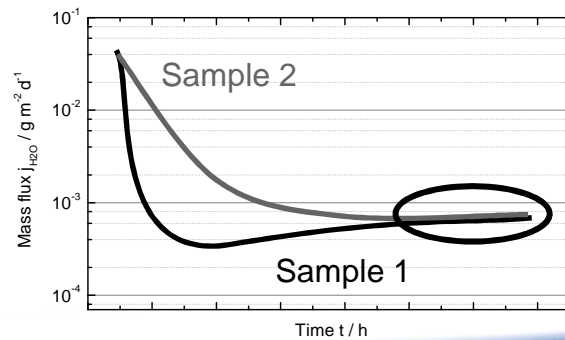
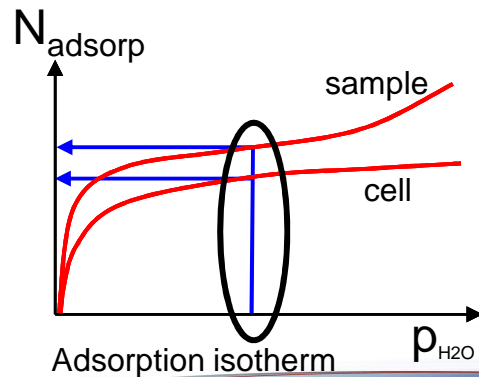


General balance equation

$$n = (\dot{n}_{\text{in}} + \dot{n}_{\text{perm}} + \dot{n}_{\text{sorpt}} + \dot{n}_{\text{leak}} - \dot{n}_{\text{out}}) \cdot \Delta t + n_o$$

Steady-state conditions

$$\begin{aligned} \dot{n}_{\text{sorption}} &= \dot{n}_{\text{desorption}} - \dot{n}_{\text{adsorption}} = 0 \\ p - p_0 &= 0 \\ n - n_0 &= (\dot{n}_{\text{perm}} - \dot{n}_{\text{out}}) \cdot \Delta t = \text{const.} \end{aligned}$$

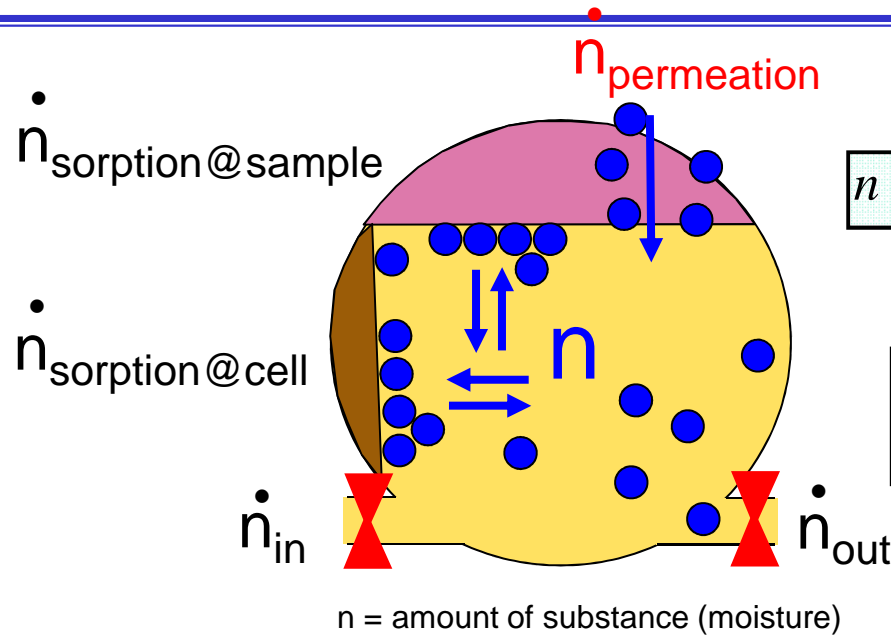


Calculation of WVTR

$$n = (\dot{n}_{\text{perm}} - \dot{n}_{\text{out}}) \cdot \Delta t + n_o$$

$$WVTR = \frac{\dot{V}_{\text{Purge}} \cdot M_{\text{H}_2\text{O}}}{R \cdot T \cdot A_{\text{Sample}}} \cdot p \cdot \frac{\phi}{1 - \phi}$$

Balance equation for static setup



General balance equation

$$n = (\dot{n}_{\text{in}} + \dot{n}_{\text{perm}} + \dot{n}_{\text{sorpt}} + \dot{n}_{\text{leak}} - \dot{n}_{\text{out}}) \cdot \Delta t + n_o$$

„non constant“ conditions

$$\dot{n}_{\text{in}} = \dot{n}_{\text{out}} = 0; \quad \dot{n}_{\text{perm}} = \text{const}$$

$$\dot{n}_{\text{sorption}} = \dot{n}_{\text{adsorption}} - \dot{n}_{\text{desorption}} > 0; \quad p - p_0 > 0$$

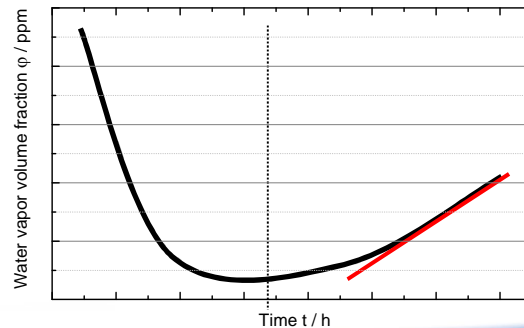
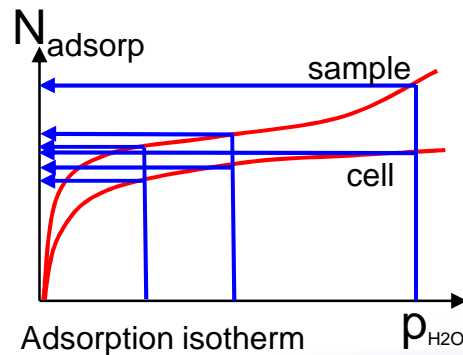
Calculation of WVTR

$$n = (\dot{n}_{\text{perm}} + \dot{n}_{\text{sorpt}}) \cdot \Delta t + n_o$$

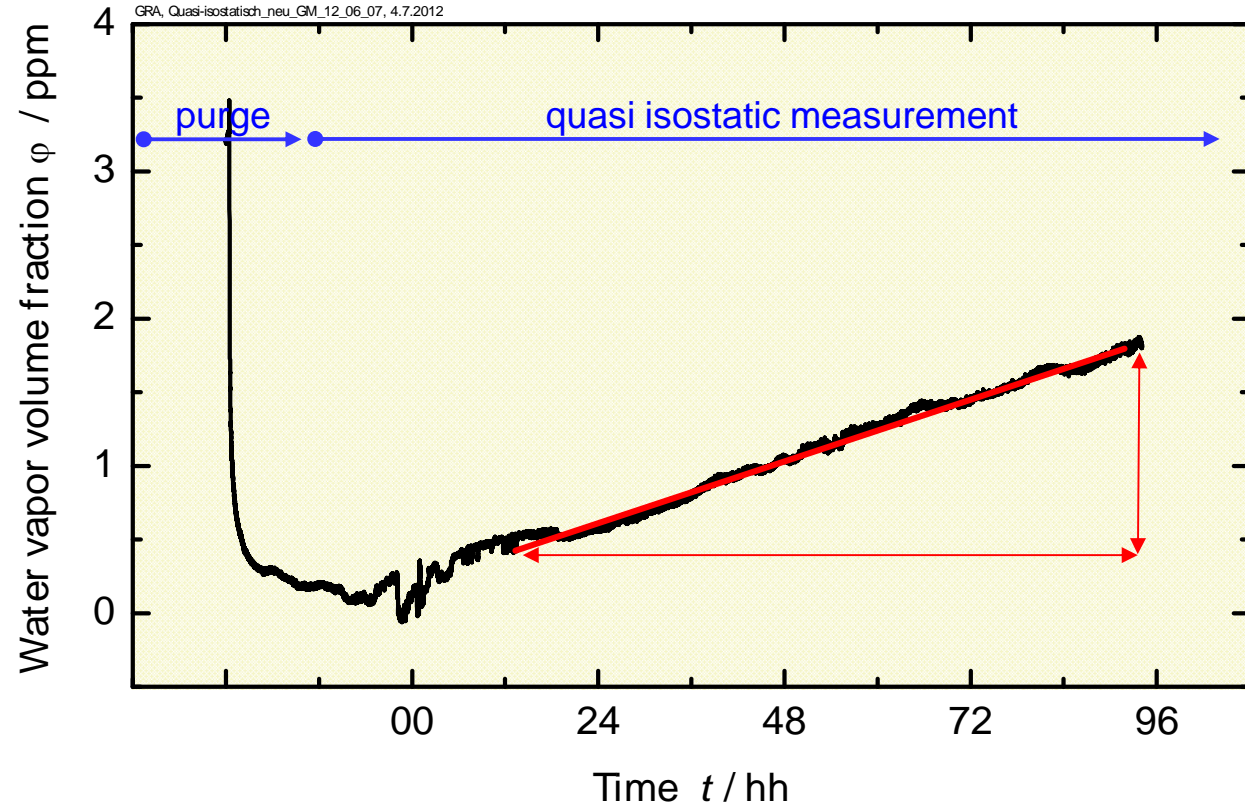
$$WVTR = \dot{n}_{\text{perm}} \cdot \frac{M_{H_2O}}{A_{\text{Sample}}} = \frac{\Delta n}{\Delta t} \cdot \frac{M_{H_2O}}{A_{\text{Sample}}}$$

$$WVTR = \frac{V_{\text{cell}}}{R \cdot T} \cdot \frac{M_{H_2O}}{A_{\text{Sample}}} \cdot \frac{p \cdot \Delta \varphi}{\Delta t}$$

$$WVTR - \dot{n}_{\text{sorp}} = \frac{V_{\text{cell}}}{R \cdot T} \cdot \frac{M_{H_2O}}{A_{\text{Sample}}} \cdot \frac{p \cdot \Delta \varphi}{\Delta t}$$



Static measurement: Background level

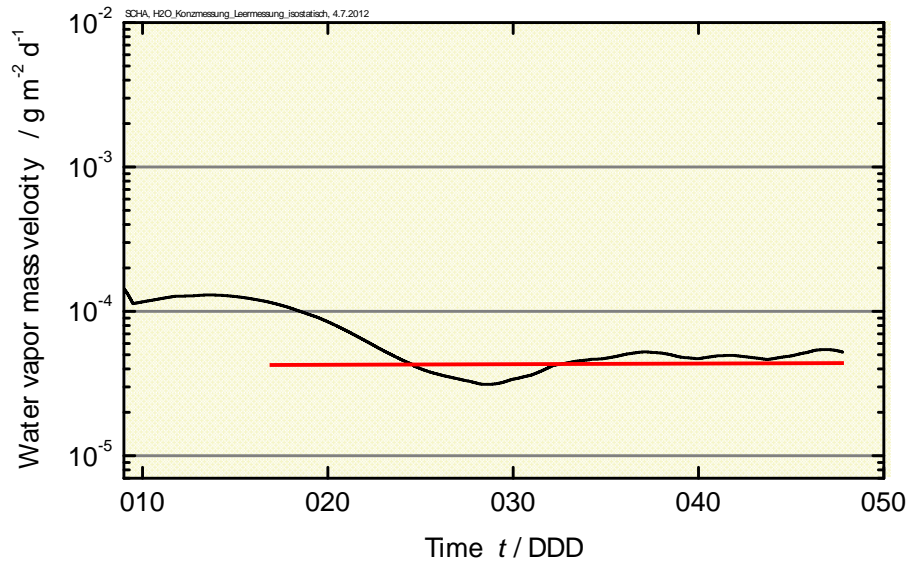


Measured background level
(sample: stainless steel)
@ 38°C / 90% r.H.

$$WVTR_{qis} = 2,5 \times 10^{-6} \text{ g m}^{-2} \text{ d}^{-1}$$

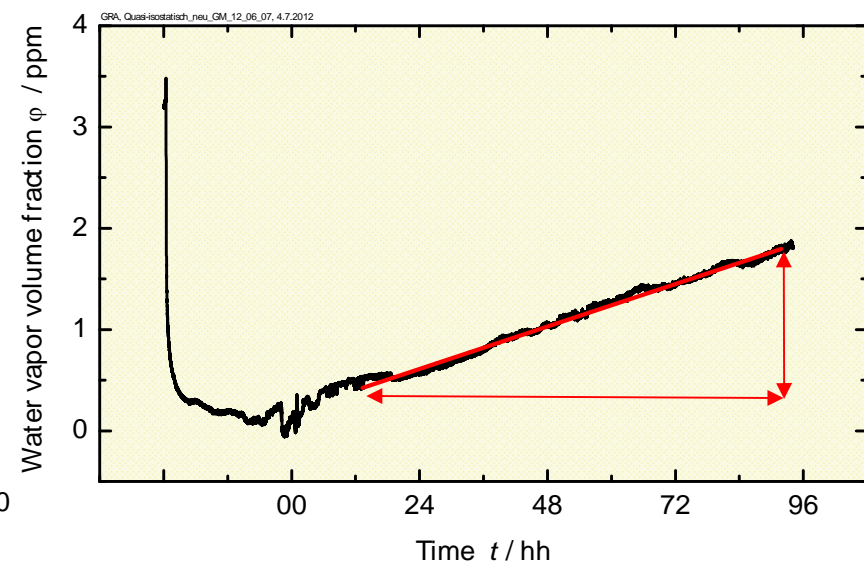
Dynamic vs. Static: background level

Dynamic setup



$$\text{WVTR}_{\text{qis}} = 5 \times 10^{-5} \text{ g m}^{-2} \text{ d}^{-1}$$

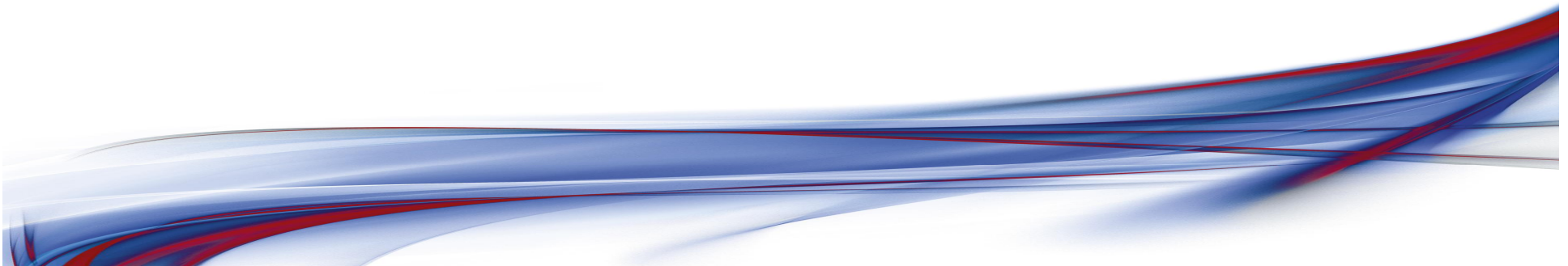
Static setup

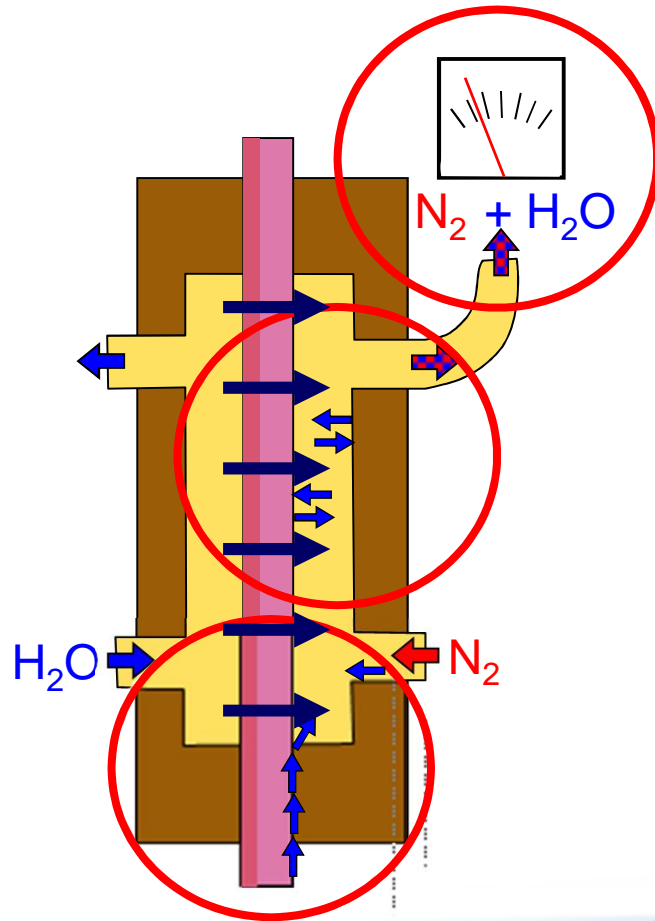


$$\text{WVTR}_{\text{qis}} = 2,5 \times 10^{-6} \text{ g m}^{-2} \text{ d}^{-1}$$

Measured background level (sample: stainless steel) @ 38°C / 90% r. H.

PPRODUCT IMPLEMENTATION



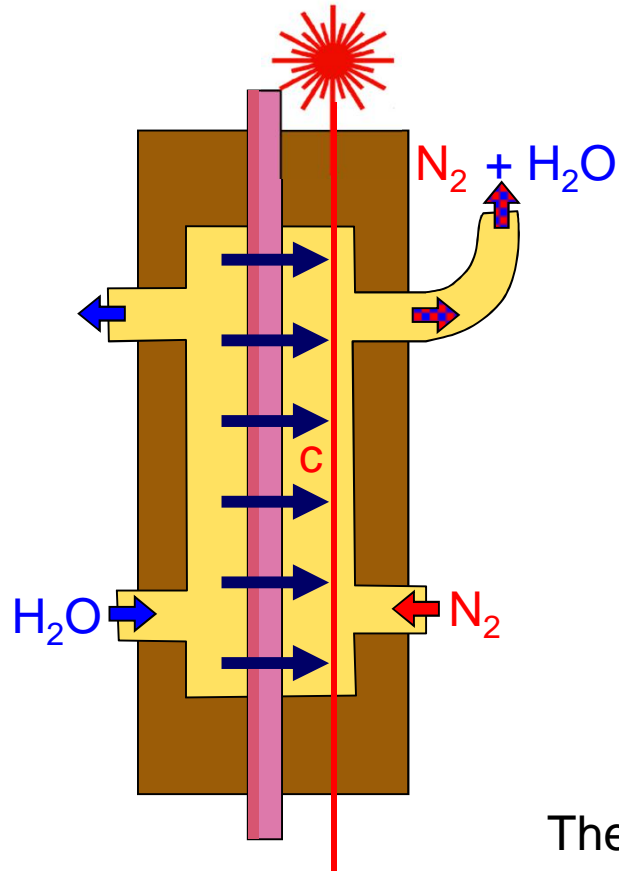


Sensor sensitivity

Adsorption / desorption of moisture

Sealing of the test cell

Parameters for tuning the sensitivity



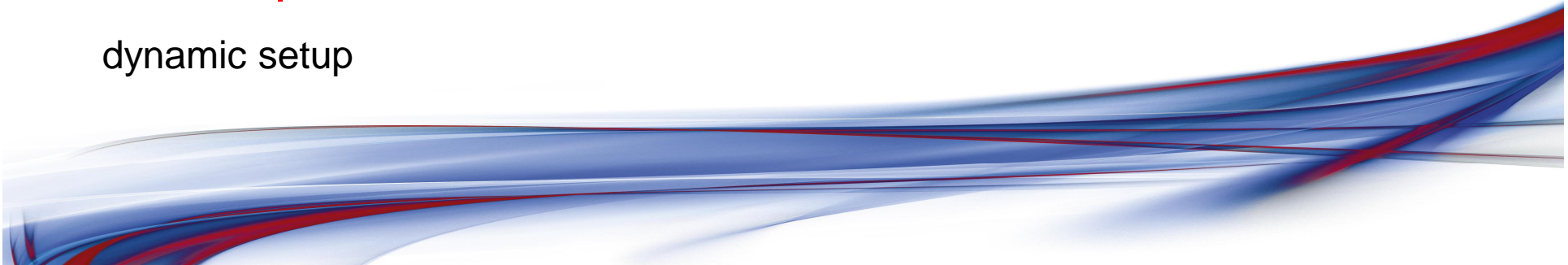
- Optical path length
- Carrier gas flow $\rightarrow c$
- Sample area $\rightarrow c$
- Selection of absorption line

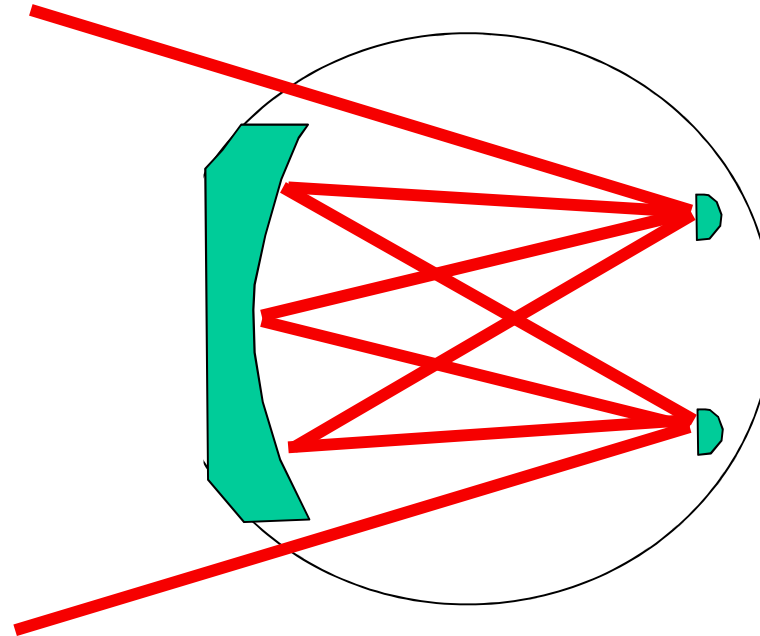
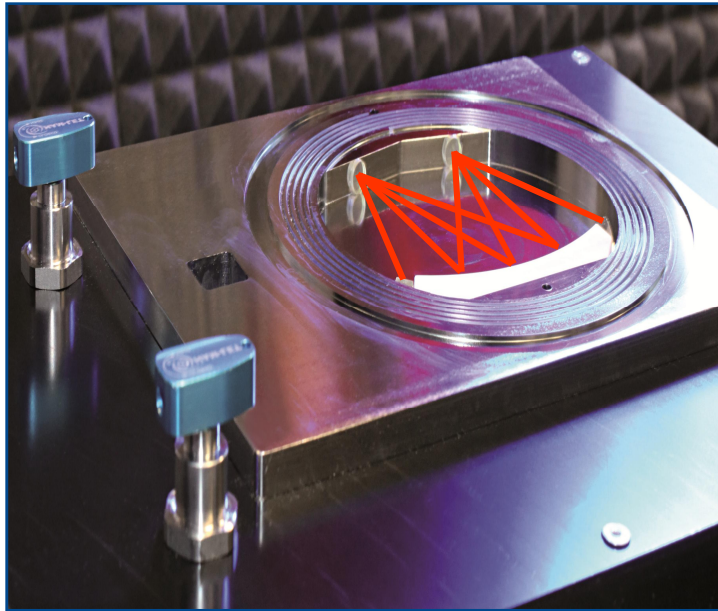
$$-\ln \frac{I(\lambda)}{I_o(\lambda)} = \varepsilon_{\lambda} \cdot c \cdot d$$

Theoretical sensitivity

LOD = 150 ppb m

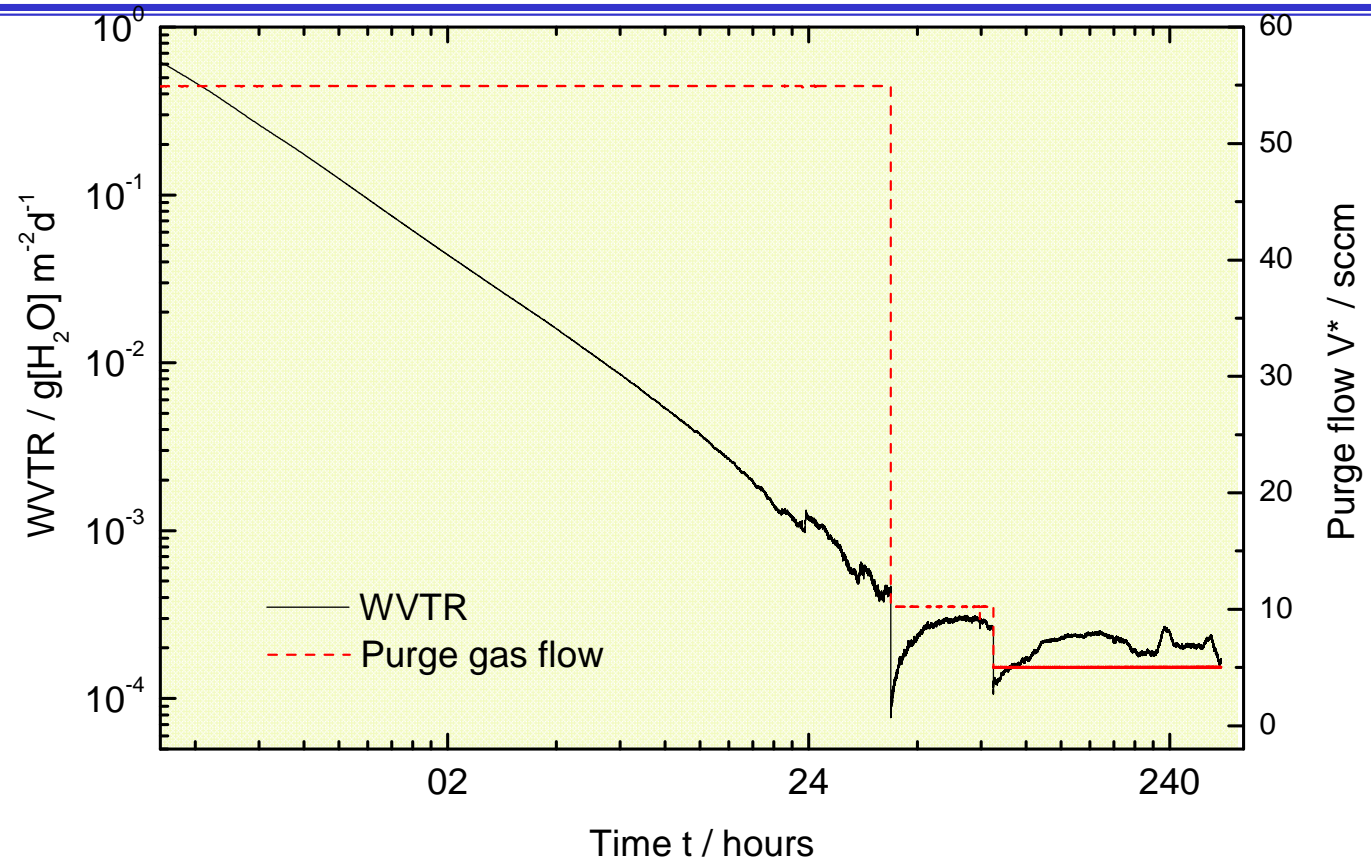
dynamic setup





Multipath design in HiBarSens®
2 m optical path length by multi 20 reflections

Tuning sensitivity: Carrier gas flow



Carrier gas flow
3 sccm - 50 sccm

Boost the sensitivity
by factor 16!

Sensor sensitivity: the laser as a sensor

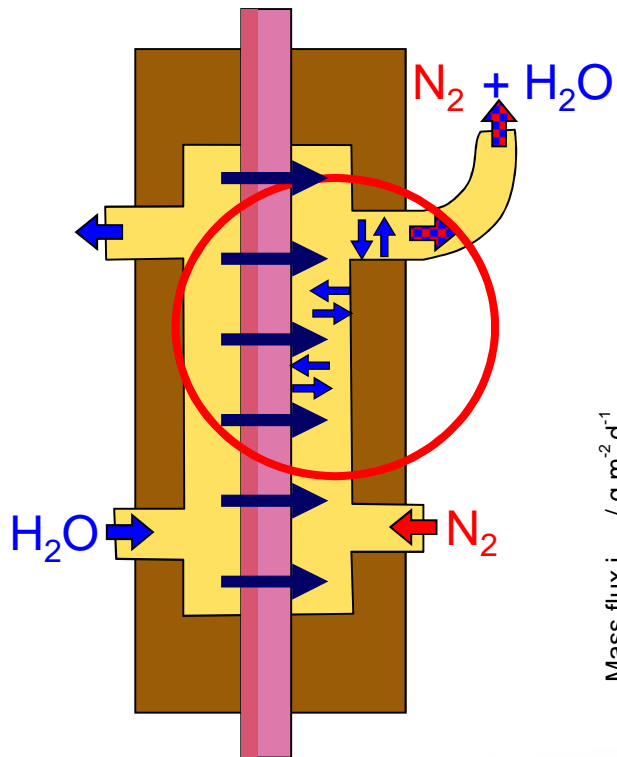
Further advantages



- High dynamic range: ppb - % ($10^{-5} - 1 \text{ g m}^{-2} \text{ d}^{-1}$)
- Very high selectivity
- Immune to high concentrated moisture
- Long time stable, no drift, no hysteresis
- Low-maintenance
- Change of target permeate by change of the laser diode
- Allows the realization of a compact design
- Easy to use

Tunable Diode Absorption Spectroscopy (TDLAS) is a non-invasive, high sensitive, high selective sensor for detection of moisture traces!

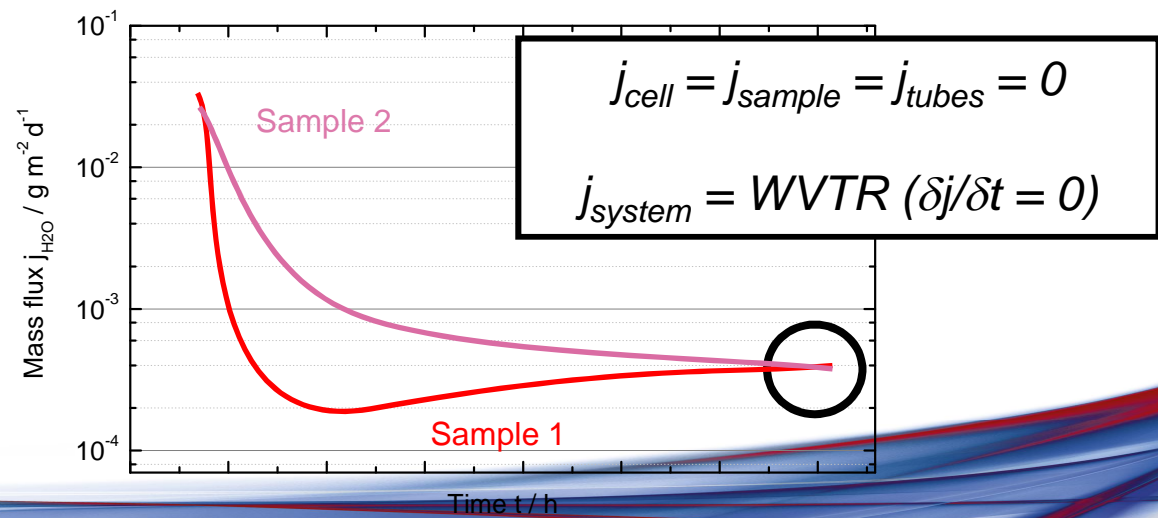
Adsorption / desorption of moisture



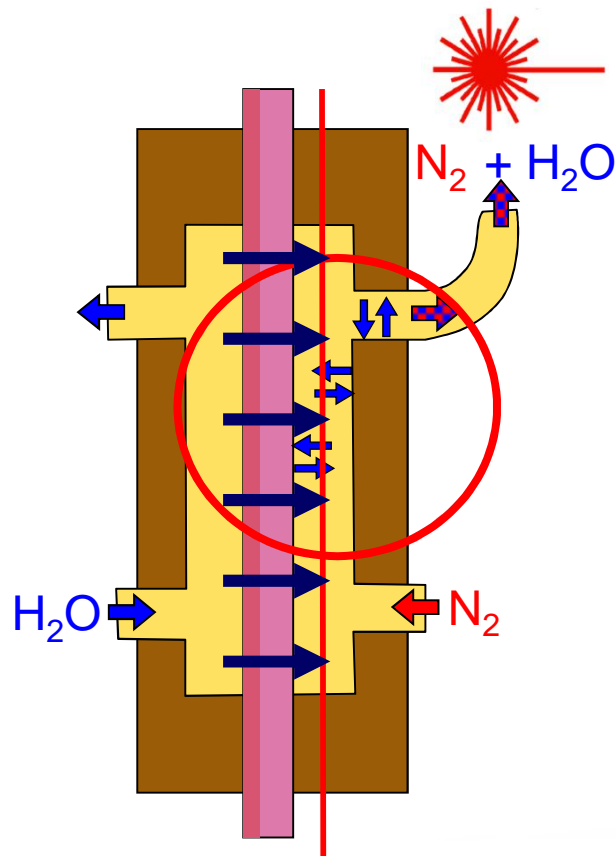
$$j_{system} = WVTR + j_{cell} + j_{sample} + j_{tubes}$$

Mass flux

$$j_x \left[\frac{g}{m^2 \cdot d} \right] = \frac{\Delta m_{H_2O} [g]}{A_x [m^2] \cdot \Delta t [d]}$$



Adsorption / desorption of moisture

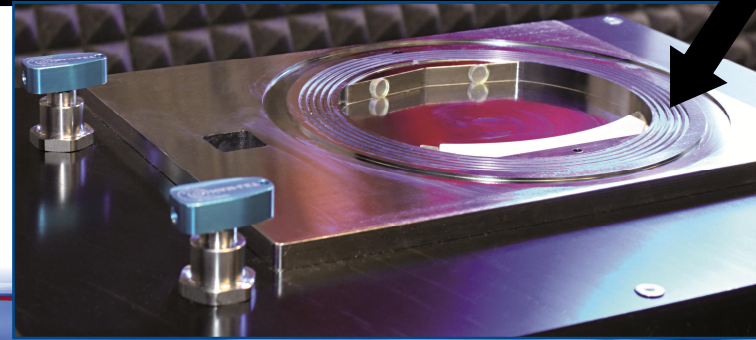
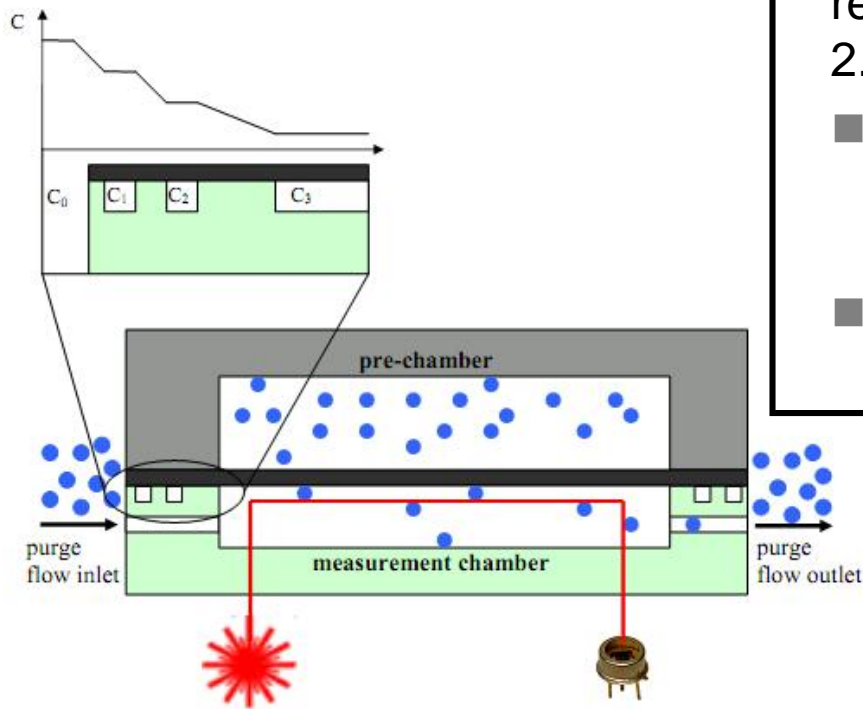


- Steady state conditions are required
 - As small as possible surface area of the cell in contact with moisture
 - Ultra smooth surfaces
 - Avoid any problematic materials inside the cell
 - Highest temperature stability
- HiBarSens - realization
 - Volume and surface vs. sample area optimized cell design
 - Electro-polished surfaces
 - Temperature stability $< 0,5^{\circ}C$
 - Sensor is placed inside the test cell

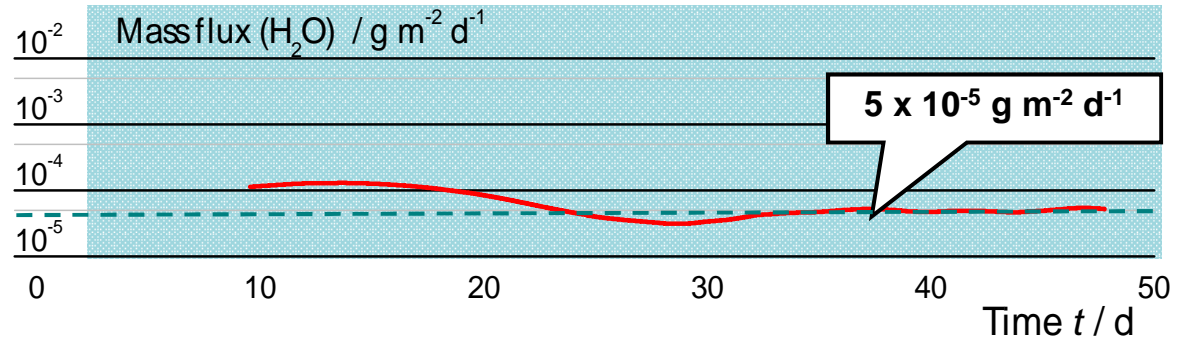
Sealing of test (measuring) cell

$$\text{Mass flux: } j_{\text{system}} = \text{WVTR} + j_{\text{cell}} + \dots + j_{\text{leakage}}$$

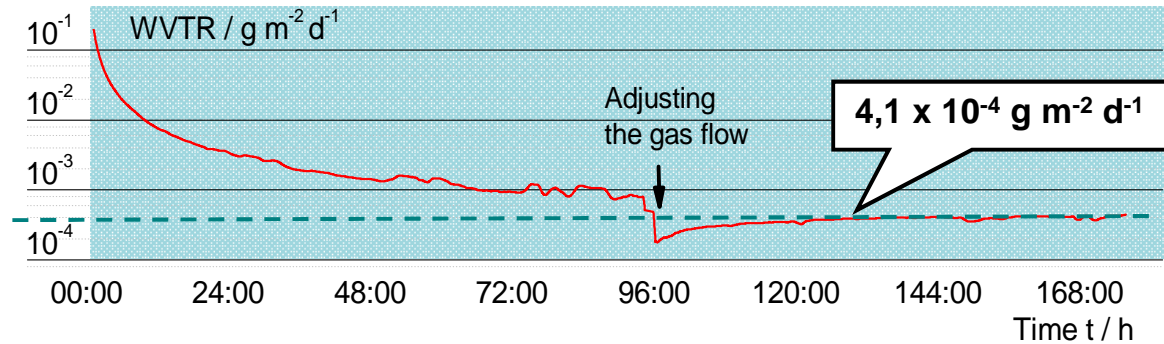
- Sample clamping has to follow the requirement for leakage rates of $2.4\text{E-}9 \text{ mbar}\cdot\text{l/s}$
 - Substitution of the classical concept (polymer O-rings) by the concept of an “active sealing”
 - Purge channels prevent ambient moisture diffusion into the cell



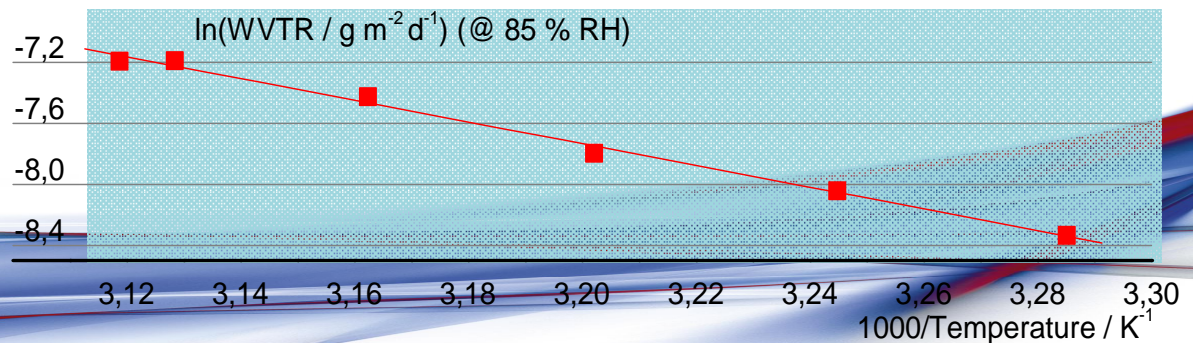
Measured background level
(sample: stainless steel)

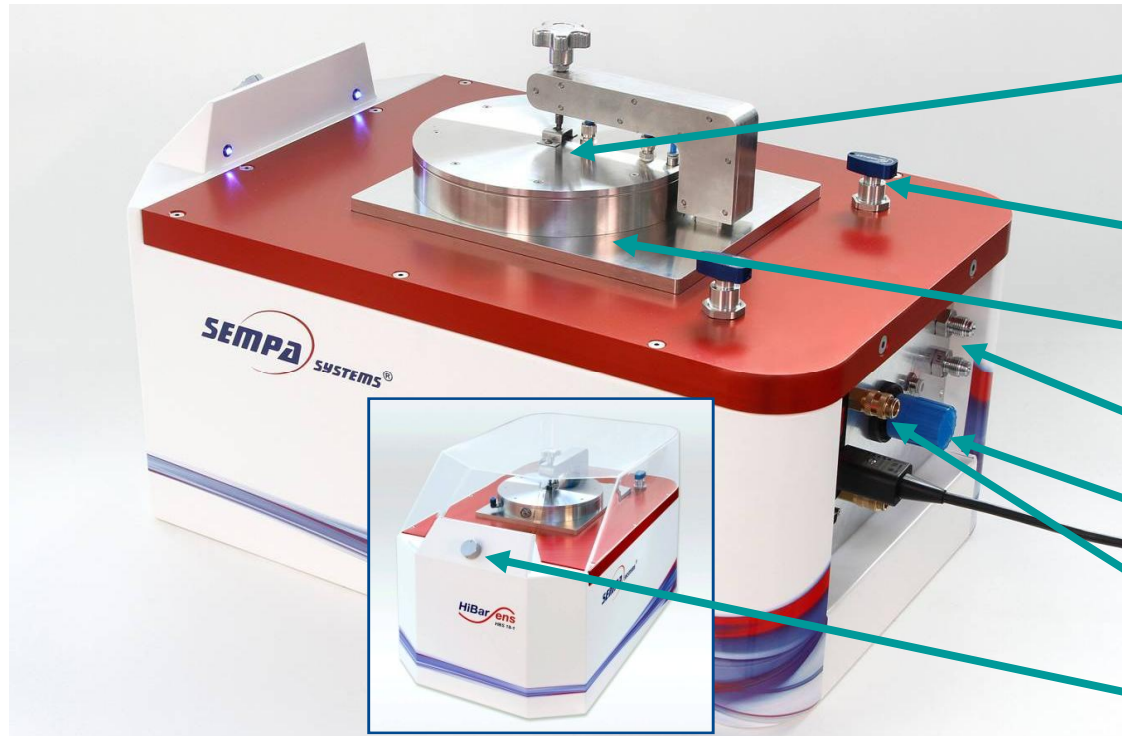


WVTR-measurement
of ultra barrier sample
(Fraunhofer POLO)



Temperature dependence
of ultra barrier sample
(for photovoltaic)





Permeation cell
- tempered
- integrated moisture generator
- Gentle clamping of the test sample

Purifier valve

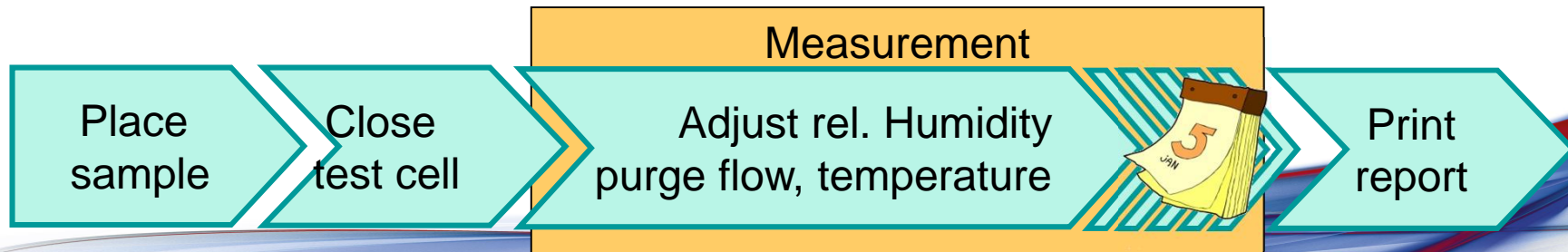
Sample

N₂ purge gas in /out

Rel. Humidity controller

Connectors for thermostat

Flow controller



- HiBarSens laser based sensor technology for highly sensitive determination of water vapor transmission rates of ultra barrier samples
- HiBarSens provides reliable measurements of WVTR down to $10^{-5} \text{ g m}^{-2} \text{ d}^{-1}$ with the potential to $10^{-6} \text{ g m}^{-2} \text{ d}^{-1}$
- HiBarSens is available as a compact, easy to use table top device





responsible for manufacturing and sales

Johannes Grüber

Kurt Pietsch



Harald Beese

Wulf Grählert

